

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ASMP.104DV1	APPLICATION NO. 10/708,624
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Akira SHIMIZU, et al.	
		FILING DATE November 12, 2003	GROUP 1725

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
M	1. 4,804,431	02/14/89	Aaron RIBNER			
M	2. 4,910,042	03/20/90	Jiri HOKYNAR			
M	3. 5,023,056	06/11/91	Monti E. AKLUFI, et al.			
M	4. 5,489,362	02/06/96	Heinz STEINHARDT, et al.			
M	5. 5,795,831	08/18/98	Izumi NAKAYAMA, et al.			
M	6. 5,954,911	09/21/99	Eric J. BERGMAN, et al.			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
M	7.	D.F. Weston, et al. HF vapor phase etching (HF/VPE): Production viability for semiconductor manufacturing and reaction model, J. Vac. Scie. Technol., 17(1) Jan./Feb. 1980, 1980 American Vacuum Society, pp. 466-468.

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EXAMINER	DATE CONSIDERED
M as dulu	3-5-03
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 809; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	